

	Hits	Search Text	DBs
1	4	((photoresist or resist) same ((dual near9 damascene) or (multi\$5level near8 profile) or (stepp\$4 near4 profile)) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask)) same (partial\$3 near6 transmit\$5) same opaque same (transparent or (ful\$2 near5 transmit\$5)) same (region or areas or location))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	4	((photoresist or resist) same ((dual near9 damascene) or (multi\$5level near8 profile) or (stepp\$4 near4 profile)) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask)) same ((partial\$3 or variable or vary\$4 or differentia\$4) near6 transmit\$5) same (opaque or block\$4 or non-transparent) same (transparent or (ful\$2 near5 transmit\$5)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	4	((photoresist or resist) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask) same (expos\$4 or illuminat\$4 or irradiat\$4) same thickness same (variat\$4 or vary\$4 or non\$3uniform\$4)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$3 or variable or vary\$4 or differentia\$4) near6 transmit\$5) same (opaque or block\$4 or non\$4transparent) same (transparent or (ful\$2 near5 transmit\$5)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	5	((photoresist or resist) same ((dual near9 damascene) or (multi\$5level near8 profile) or (stepp\$4 near4 profile)) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$3 or variable or vary\$4 or differentia\$4) near6 transmit\$5) same (opaque or block\$4 or non\$4transparent) same (transparent or (ful\$2 near5 transmit\$5)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	11	((photoresist or resist) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask) same (expos\$4 or illuminat\$4 or irradiat\$4) same (variable or different\$3 or differ\$4 or chang\$4) same intensit\$4) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$3 or variable or vary\$4 or differentia\$4) near6 transmit\$5) same (opaque or block\$4 or non\$4transparent) same (transparent or (ful\$2 near5 transmit\$5)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	11	((photoresist or resist) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask) same (expos\$4 or illuminat\$4 or irradiat\$4) same (variable or different\$3 or differ\$4 or chang\$4) same dosage) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same (partial\$4 or transparent or (fully\$4transmit\$4) or block\$4 or opaque or variable) same transmit\$5 same (phase near5 shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	4	((("6482554") or ("6355399") or ("6242344") or ("5753417"))).PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
8	53	((photoresist or resist) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask) same (variable or different\$3 or differ\$4 or chang\$4 or vary\$3) same thickness\$4) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and ((opaque or chrome) near6 (film or layer or coat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	43	((photoresist or resist) same ((upper near9 layer) or (lower near9 layer) or dual or double or two\$3layer\$3 or (top near9 layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device) same (reticle or mask\$3 or phase\$4shift\$4mask or photomask)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
10	57	((photoresist or resist) same ((upper or top or two or second or double) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	56	((photoresist or resist) same ((upper or top or two or second or double) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device) same (reticle or photomask or mask or (phase near9 mask))) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	4	((photoresist or resist) same ((upper or top or second) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device) same (reticle or photomask or mask or (phase near9 mask)) same (tri\$3tone or tri\$4 near5 level or multi\$4 near4 level or gray\$3scale)) and (dual near6 damascene)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	36	((photoresist or resist) same ((upper or top or second) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or mask or (phase near9 mask)) same (tri\$3tone or (tri\$4 near5 level) or (multi\$4 near4 level) or gray\$3scale)) and (dual near6 damascene)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	5	430/311.ccls. and ((photoresist or resist) same ((upper or top or two or second or double or dual) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	23	430/312.ccls. and ((photoresist or resist) same ((upper or top or two or second or double or dual) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3 or first) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome or ((first or second or third) near6 transmit\$6)) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	32	430/396.ccls. and ((photoresist or resist) same ((upper or top or two or second or double or dual) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3 or first) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and ((opaque or chrome or ((first or second or third) near6 transmit\$6)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	201	430/5.ccls. and ((photoresist or resist) same ((upper or top or two or second or double or dual) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3 or first) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and ((opaque or chrome or ((first or second or third) near6 transmit\$6)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB